



# Cost Effective Viafill Electroplating on HDI Application

# 应用在HDI具成本效率 之填盲孔电镀铜技术

## MICROFILL™ EVF 15 Acid Copper

Along with denser circuit and smaller via holes trend, to manufacture high reliability HDI board under reasonable cost becomes a tough challenge. In order to conquer it, leading chemical supplier Dow newly launched MICROFILL™ EVF 15, the product can demonstrate good via filling performance at thin plating thickness, also achieve other advantages like process flow minimization, productivity increment, and cost effectiveness. Benefit high-end HDI (microvia filling and through-hole plating) customers on both product quality and cost.

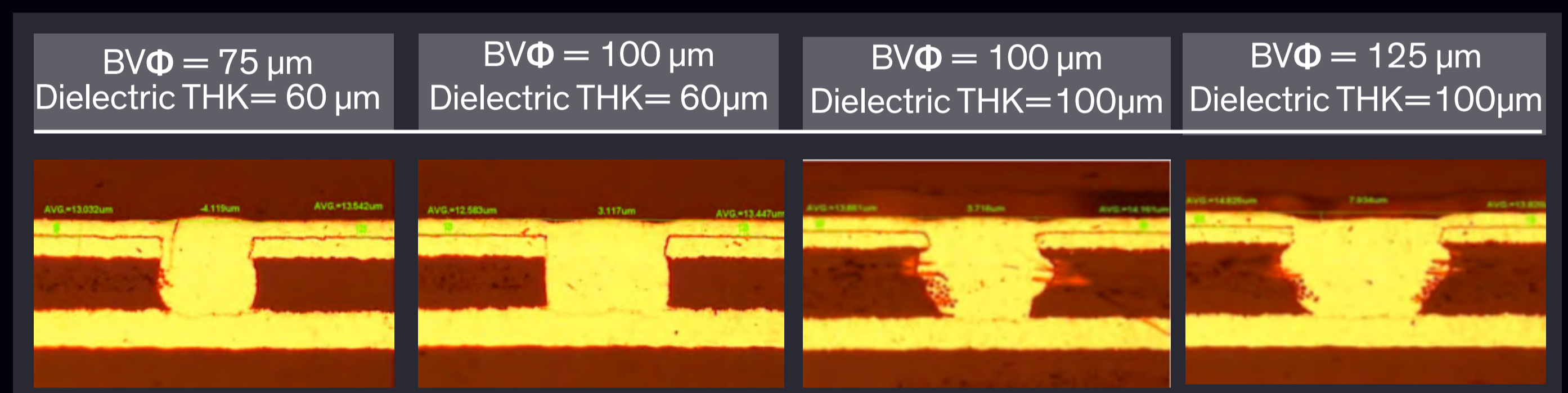
在HDI产业走向高线路密度以致孔径日益细微化的时代, 欲以合理成本制作出稳定电性表现的HDI板挑战重重。为了克服困难, 业界化学品领导供应商陶氏电子材料推出新世代填孔电镀技术MICROFILL™ EVF 15 酸铜药水。该药水可在相对薄的电镀厚度下展现良好填孔效果, 达到缩减制程, 提升生产效率与成本效率, 满足高阶HDI (盲孔填孔和电镀通孔结构) 客户同时追求产品品质和成本效率最佳化之目标。

### Advantages 优点

- Exceptional microvia filling performance on HDI application  
在HDI板上展现卓越的盲孔电镀填孔表现
- Capable on microvia filling and through-hole plating  
可同时应用于盲孔填孔和电镀通孔
- DC process with insoluble anodes for simple operation and elimination of idle time effects  
药水在搭配不溶性阳极与直流电镀设备下操作容易, 产线闲置重启后的稳定度高
- Designed for panel and pattern plate applications  
可同时应用于全板及二次铜电镀
- Bright, highly ductile, leveled deposits  
镀铜表面具高亮度、高延展性、以及平整性
- Easily analyzed and controlled by conventional CVS  
所有化学药液都可采用CVS分析控制
- Highly flexible process for different end user requirements  
具备弹性的生产流程

### Performance 效能

Performance at Microvia (BV)  
(Plating Thickness = 15µm @2 ASD)



Performance at Through Hole (TH) Result:  
TP% and Knee TP% >80%

Surface Thickness = 30µm @ 2 ASD  
TH Ø = 9.8 mil (AR=5.6)  
Core Thickness = 55 mil  
Board Thickness: 1.0-1.4mm

